

**PATENT** 

2/05

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Yoshikazu Nagamura, et al.

Serial No.:

(Divisional of Serial No. 09/504,728)

Group Art Unit:

Filed: February 09, 2001

Examiner:

For:

METHOD OF AND APPARATUS FOR WASHING PHOTOMASK AND WASHING

SOLUTION FOR PHOTOMASK

## PRELIMINARY AMENDMENT

Commissioner for Patents Washington, DC 20231

Sir:

Prior to examination of the above-referenced application, please amend the application as

follows:

IN THE CLAIMS:

Claim 6, line 2, change "also employing ultrasonics waves in said first step of claim 1" to

--wherein said step of removing organic matter and metal impurities employs ultrasonics waves--

## **REMARKS**

Entry of this preliminary amendment is respectfully requested.

Respectfully submitted,

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